Electronic Patent Application Fee Transmittal									
Application Number:	10672778								
Filing Date:	26-Sep-2003								
Title of Invention:	Atomic layer deposition (ALD) method with enhanced deposition rate								
First Named Inventor:	Chih-Ta Wu								
Filer:	Daniel R. McClure								
Attorney Docket Number:	252016-3000								
Filed as Large Entity									
Utility Filing Fees									
Description		Fee Code	Quantity	Amount	Sub-Total in USD(\$)				
Basic Filing:									
Pages:									
Claims:									
Miscellaneous-Filing:									
Petition:									
Patent-Appeals-and-Interference:									
Post-Allowance-and-Post-Issuance:									
Extension-of-Time:									
Extension - 1 month with \$0 paid		1251	1	120	120				

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)	
Miscellaneous:					
Request for continued examination	1801	1	790	790	
	Tota	Total in USD (\$)			